Jay Mody

List of Publications by Year in descending order

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933447 1058476 23 412 10 14 h-index citations g-index papers 24 24 24 372 docs citations times ranked citing authors all docs

#	Article	IF	CITATIONS
1	Evolution of metastable phases in silicon during nanoindentation: mechanism analysis and experimental verification. Nanotechnology, 2009, 20, 305705.	2.6	109
2	Atom-probe for FinFET dopant characterization. Ultramicroscopy, 2011, 111, 535-539.	1.9	51
3	Observation of diameter dependent carrier distribution in nanowire-based transistors. Nanotechnology, 2011, 22, 185701.	2.6	42
4	Analysis and modeling of the high vacuum scanning spreading resistance microscopy nanocontact on silicon. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2010, 28, 401-406.	1.2	39
5	Experimental studies of dose retention and activation in fin field-effect-transistor-based structures. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2010, 28, C1H5-C1H13.	1.2	26
6	Dopant/carrier profiling for 3D-structures. Physica Status Solidi C: Current Topics in Solid State Physics, 2014, 11, 121-129.	0.8	23
7	Two-dimensional carrier mapping at the nanometer-scale on 32nm node targeted p-MOSFETs using high vacuum scanning spreading resistance microscopy. Solid-State Electronics, 2012, 71, 69-73.	1.4	18
8	Physical degradation of gate dielectrics induced by local electrical stress using conductive atomic force microscopy. Journal of Applied Physics, 2009, 106, .	2.5	17
9	3D-carrier profiling in FinFETs using scanning spreading resistance microscopy., 2011,,.		15
10	Impact of the environmental conditions on the electrical characteristics of scanning spreading resistance microscopy. Journal of Vacuum Science & Technology B, 2008, 26, 338.	1.3	13
11	Toward extending the capabilities of scanning spreading resistance microscopy for fin field-effect-transistor-based structures. Journal of Vacuum Science & Technology B, 2008, 26, 351.	1.3	11
12	Dopant and carrier profiling in FinFET-based devices with sub-nanometer resolution. , 2010, , .		11
13	High performance n-MOS finFET by damage-free, conformal extension doping. , 2011, , .		6
14	Dopant and carrier profiling for 3D-device architectures. , 2011, , .		5
15	Subnanometer Characterization of Nanoelectronic Devices., 2013,, 677-704.		5
16	Atom Probe Tomography for 3D-dopant analysis in FinFET devices. , 2012, , .		4
17	Understanding device performance by incorporating 2D-carrier profiles from high resolution scanning spreading resistance microscopy into device simulations. Solid-State Electronics, 2012, 74, 38-42.	1.4	4
18	Scanning Spreading Resistance Microscopy For 3D-Carrier Profiling in FinFET-based Structures. Materials Research Society Symposia Proceedings, 2008, 1070, 1.	0.1	3

#	Article	IF	CITATIONS
19	Mapping Conductance and Carrier Distributions in Confined Three-Dimensional Transistor Structures. Nanoscience and Technology, 2019, , 71-106.	1.5	3
20	Scanning spreading resistance microscopy for carrier profiling beyond 32nm node., 2012,,.		1
21	Non-Destructive Characterization of Activated Ion-Implanted Doping Profiles Based on Photomodulated Optical Reflectance. , $2011, , .$		O
22	Understanding device performance by incorporating 2D-carrier profiles from high resolution scanning spreading resistance microscopy into device simulations., 2011,,.		0
23	Two-dimensional carrier mapping at the nanometer-scale on 32nm node targeted p-MOSFETs using high vacuum scanning spreading resistance microscopy. , 2011, , .		0